

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
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GARO DERDERIAN
GURTEJ S. SANDHU
WEIMIN M. LI
MARK VISOKAY
CEM BASCERI
SAM YANG

Serial No.: 09/590,795

Filed: June 8, 2000

For: METHODS FOR FORMING AND
INTEGRATED CIRCUIT STRUCTURES
CONTAINING RUTHENIUM AND
TUNGSTEN CONTAINING LAYERS

Confirmation No.: 9849

Group Art Unit: 2818

Examiner: David Vu

Atty. Dkt. No.: 2008.010100
(formerly 6047-53173)

Customer No.: 23720

RESPONSE TO FINAL OFFICE ACTION DATED MARCH 20, 2006

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This paper is submitted in response to the Final Office Action dated March 20, 2006, for which the two-month date for response is May 20, 2006.

No fees are believed to be due in connection with the present document. However, should any fees be required under 37 C.F.R. §§ 1.16 to 1.21, the Director is authorized to deduct such fees from Williams, Morgan & Amerson, P.C. Deposit Account No. 50-0786/2008.001010.

Reconsideration of the application in view of the following remarks is respectfully requested.